

Abstract

AQUEOUS DISPERSION, PROCESS FOR ITS PRODUCTION AND USE

Aqueous dispersion containing a silicon-aluminum mixed oxide powder, the powder containing 0.1 to 99.9 wt.% Al_2O_3 and Si-O-Al-bonds. The dispersion can be produced using dispersing and/or grinding devices which achieve an energy input of at least 200 KJ/m³. The dispersion can be used for the chemical-mechanical polishing of semiconductor substrates.